|   | Application No.  | Applicant(s)   |                         |
|---|--|--|-------------------------|
| Notice of Allowability  | 10/748,286   | NOGUCHI ET AL.   | (CINO                   |
|   | Examiner   | Art Unit   | •                       |
|   | Laura M. Schillinger   | 2813   |                         |
| The MAILING DATE of this communication app<br>All claims being allowable, PROSECUTION ON THE MERITS IS<br>herewith (or previously mailed), a Notice of Allowance (PTOL-85<br>NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT I<br>of the Office or upon petition by the applicant. See 37 CFR 1.31  | S (OR REMAINS) CLOSED in<br>5) or other appropriate commu<br>RIGHTS. This application is s   | this application. If not included in this application will be mailed in due c  | d<br>ourse. <b>THIS</b> |
| 1. X This communication is responsive to 12/31/03.  |  |  |                         |
| 2. ☑ The allowed claim(s) is/are <u>1-10</u> .  |  |  |                         |
| 3.   The drawings filed on 31 December 2003 are accepted b  | y the Examiner.  |  |                         |
| <ul> <li>4.  Acknowledgment is made of a claim for foreign priority of a)  All b)  Some* c)  None of the: <ol> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON </li> </ul> | ve been received.  ve been received in Application ocuments have been received  " of this communication to file  | n No<br>d in this national stage applicati   |                         |
| THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be sub INFORMAL PATENT APPLICATION (PTO-152) which gi  | mitted. Note the attached EXA  | AMINER'S AMENDMENT or NO   | OTICE OF                |
| 6. CORRECTED DRAWINGS (as "replacement sheets") m  (a) including changes required by the Notice of Draftspe  1) hereto or 2) to Paper No./Mail Date  (b) including changes required by the attached Examine Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in T. DEPOSIT OF and/or INFORMATION about the depattached Examiner's comment regarding REQUIREMENT   | ust be submitted.  Irson's Patent Drawing Review  Ir's Amendment / Comment of  1.84(c)) should be written on the header according to 37 CF  DOSIT OF BIOLOGICAL MATE | w ( PTO-948) attached r in the Office action of the drawings in the front (not the R 1.121(d). ERIAL must be submitted. N  |                         |
| <ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SE Paper No./Mail Date 12/31/03)</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>  | 6. Interview S Paper No 8/08), 7. Examiner's   | Iformal Patent Application (PTC) ummary (PTO-413), /Mail Date Amendment/Comment  Statement of Reasons for Allow  Laura M Schillinger Primary Examiner Art Unit: 2813 |                         |

Application/Control Number: 10/748,286

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## **DETAILED ACTION**

## Allowable Subject Matter

Claims 1-10 are allowed.

The following is an examiner's statement of reasons for allowance:

In reference to claim 1, Ng et al (US 6709918) teaches a method comprising:

- a) preparing a semiconductor substrate (Fig.1 (7));
- b) forming, on the semiconductor substrate, a first insulation film (8) where a first interconnect (10) with copper-based first conductor film and a capacitor bottom (20A) are buried (Fig.1);
- c) forming a second insulation film (14) on the first insulation film (8) where the first interconnect (10) and the bottom electrode (20A) are buried (Fig.2);
- d) forming a third insulation film (26) on the second insulation film (14) (Fig.3);
- e) forming a first hole by removing a selected area of the third insulation film (Fig.4 (26));
- f) forming a capacitor top electrode (24A) with a second conductor film in the first hole (Fig.4- note that layer 24A may be considered "in" the hole as claimed due to the etching of holes on both sides of layer 24A- the Examiner considers this "in the first hole);
- g) forming a fourth insulation film (30) on the third insulation film (26) where the top electrode (24A) is buried (Fig.5);

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h) forming a second hole(6) and a third hole (6) to expose the top electrode (24A) by removing a selected are of the fourth insulation film (30), and forming a fourth hole (6) (Fig. 5) and

i) filling a copper-based third conductor film into the second hole, the third hole and the fourth hole (Fig.6 and Col.6, lines: 35-50).

However, Ng et al ('918) fails to teach nor suggest Applicant's additional claimed limitation of step (h) which includes forming a fourth hole to expose the first interconnect by removing selected areas of the third insulation film and the second insulation film at the bottom of the second hole. In contrast, the damascene copper interconnects are already formed to connect to underlying interconnect layer 10 (Fig.7) therefore there is no suggestion to modify Ng to further include an additional contact hole extending to the interconnect layer as claimed by the Applicant. Claim 1 therefore contains allowable subject matter. Claims 2-10 act to further narrow independent claim 1 and are therefore also in condition for allowance.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Laura M. Schillinger whose telephone number is (571) 272-1697. The examiner can normally be reached on M-T, R-F 7:00-5:00.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl W. Whitehead, Jr. can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

4/1/05

Laura M Schillinger Primary Examiner Art Unit 2813